Gelest Showcases Wide Array of Volatile Carbosilanes For Electronics Applications

MORRISVILLE, Pa. (September 28, 2012) -- Gelest’s newest reference piece, “Volatile Carbosilanes,” features preeminent precursors for silicone carbide films and buffer layers; carbon-doped (tensile-strained) silicon; ALD promoted patterning and seed layers; SiCO:H films for low-k, barrier layers, and etch-stop; and silicon carbonitride utilized in the passivation of silicon-based photovoltaics.

To obtain a copy of “Volatile Carbosilanes” or to engage in discussions to explore solutions for your new product development initiatives, please contact: Gabrielle Horvath, Sales & Marketing Associate, at 215-547-1015 or ghorvath@gelest.com.

About Gelest
Gelest, Inc., headquartered in Morrisville, Pennsylvania, is recognized worldwide as an innovator, manufacturer and supplier of commercial and research quantities of organosilicon compounds, metal-organic compounds and silicones. Gelest serves advanced technology markets through a materials science-driven approach. The company provides focused technical development and application support for semiconductors, optical materials, pharmaceutical synthesis, diagnostics and separation science, specialty polymeric materials and cosmetics: “Gelest – Enabling Your Technology.”